

Title (en)

Electrolyte and the method of depositing metal layers especially of iron, cobalt, nickel, copper and zinc

Title (de)

Elektrolyt und Verfahren zur Anbringung von Metallschichten, insbesondere aus Eisen, Kobalt, Nickel, Kupfer und Zink

Title (fr)

Électrolyte et procédé de dépôt de couches métalliques, en particulier de fer, cobalt, nickel, cuivre et zinc

Publication

EP 2045365 A1 20090408 (EN)

Application

EP 08460009 A 20080328

Priority

PL 38211507 A 20070402

Abstract (en)

The electrolyte and the method of depositing metal layers, especially of iron, cobalt, nickel, copper and zinc to be used in electrotechnics and electroplating technology. The method of depositing metal layers, especially of iron, cobalt, nickel, copper and zinc by electrolytic deposition from the electrolyte (4) being a mixture mainly of acetone, hydrochloric acid, positive ions of the metal being deposited, is characterized in that at the initial stage of the process at least one anode (1) is being dissolved in the electrolyte (4) containing, at the initial stage, 90-99 % of acetone, 1-10 % of water and 0.5-3 % of concentrated hydrochloric acid (36 % solution HCl in water). Then the metal layer is deposited on the surface of cathode (5) and the concentration of ions of the metal, being deposited in the electrolyte (4), is set automatically. The electrolyte is characterized in that it contains 90-99 % of acetone, 1-10 % of water and 0.5-3 % of concentrated hydrochloric acid (36 % solution HCl in water).

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Citation (applicant)

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